



Revue Annuelle CMI-COMLAB

Date : mardi 4 juin 2002

Heures : 11h00 – 17h30

Lieu : Salle Polyvalente, Centre Est, CE 1 515

Programme :

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|--------------------|---|
| 11h00-11h10 | S. Catsicas , Message du Vice-Président de l'EPFL |
| 11h10-11h15 | Ph. Flückiger , Introduction |
| 11h15-11h35 | A. Perret (CSEM), Silicon as material for mechanical wrist watches |
| 11h35-11h55 | A. M. Ionescu (EPFL), EPFL technologies for merging RF MEMS with RF ICs for increased performance |
| 11h55-12h15 | U. Stauffer (IMT), Multifunctional SXM probes |
| 12h15-12h35 | P. Murali (EPFL), From bulk to surface micromachining – From micron to submicron process control |
| 12h35-14h00 | Repas au Parmentier, session posters |
| 14h00-14h20 | S. Verpoorte (IMT), Integration of contactless conductivity detection into microfluidic devices |
| 14h20-14h40 | J. Brugger (EPFL), Nano-engineering : top-down meets bottom-up |
| 14h40-15h00 | F. Cardot (CSEM), Microelectrode arrays for environmental and biomedical monitoring |
| 15h00-15h20 | C. Hibert (EPFL), Dry etching in MEMS fabrication |
| 15h20-15h30 | Pause, session posters, rafraîchissements |
| 15h30-15h45 | S. Gawad (EPFL), Impedance spectroscopy cell analysis and sorting in microchannels |
| 15h45-16h00 | C. Marxer (Sercalo), Optical MEMS for telecommunications |
| 16h00-16h15 | Ph. Krebs (Unaxis-SPTec), Additive structuration and application to SAW duplexer high power resistant metallisations |
| 16h15-16h30 | A. Hoogerwerf (CSEM), New photoresist for electroforming of micro parts |
| 16h30-17h30 | Apéritif, session posters |